

Atty. Dkt. No. 083847-0198

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Van Crocker et al.

Title:

Nanometer-Scale Engineered Structures, Methods and Apparatus for Fabrication thereof, and Applications to

Mask Repair, Enhancement, and Fabrication

Appl. No.:

10/689,547

Filing Date:

October 21, 2003

Examiner:

Ruggles

Art Unit:

1756

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

The Applicants respectfully respond to the January 26, 2006 restriction requirement with traverse and do not necessarily agree or disagree with any of the Examiner's positions stated therein to the extent they can be understood. In the meantime, however, the Applicants elect with traverse group I including claims 1-73 and 79-82. The Applicants respectfully request in particular reconsideration on one point: that group III (claim 83) be examined in this application as the additional search effort is not believed to be large.

Without generating any admissions or estoppel, the applicants also submit their species election without prejudice, electing the phase shifting photomask (no. 2 of the ten species cited). Claims readable thereon in the various embodiments as presently understood include 1-4, 6-73, and 79-82.

If the Examiner has any questions about this response, he should contact the undersigned.

The Commissioner is hereby authorized to charge any additional fees which may be required regarding this application under 37 CFR §§ 1.16-1.17, or any other provision, or credit any overpayment, to Deposit Account No. 19-0741. Should no proper payment be enclosed herewith, as by a check being in the wrong amount, unsigned, post-dated, otherwise improper or informal or even entirely missing, the Commissioner is authorized to charge the unpaid amount to Deposit Account No. 19-0741.

Respectfully submitted,

FOLEY & LARDNER LLP

Customer Number: 23533

Telephone:

(202) 672-5569

Facsimile:

(202) 672-5399

J. Steven Rutt

Attorney for Applicant Registration No. 40,153